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***Marked-Up Substitute Specification***

**Application No. 09/986,958**

**TITLE OF THE INVENTION**

**EXPOSURE APPARATUS, METHOD OF MANUFACTURING  
SEMICONDUCTOR DEVICES, SEMICONDUCTOR MANUFACTURING  
PLANT, METHOD OF MAINTAINING EXPOSURE APPARATUS, AND  
POSITION DETECTOR**

**FIELD OF THE INVENTION**

This invention relates to an exposure apparatus and, more particularly, to an exposure apparatus used when a semiconductor device or the like is manufactured in a photolithography process.

**BACKGROUND OF THE INVENTION**

A demagnifying projection exposure apparatus is used widely in the fabrication of semiconductor circuits such as LSI chips. A demagnifying projection exposure apparatus